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Lithographic apparatus and device manufacturing method

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Lithographic Apparatus and Device Manufacturing Method

The present invention relates to a lithographic projection apparatus comprising:

- a radiation system for providing a projection beam of radiation;
- a support structure for supporting patterning means, the patterning means serving to pattern the projection beam according to a desired pattern;
- 5 - a substrate table for holding a substrate;
- a projection system for projecting the patterned beam onto a target portion of the substrate; and
- a liquid supply system for at least partly filling the space between the final element of said projection system and an object positioned on said substrate table, with liquid.

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The term "patterning means" as here employed should be broadly interpreted as referring to means that can be used to endow an incoming radiation beam with a patterned cross-section, corresponding to a pattern that is to be created in a target portion of the substrate; the term "light valve" can also be used in this context. Generally, the said pattern will correspond to a particular functional layer in a device being created in the target portion, such as an integrated circuit or other device (see below). Examples of such patterning means include:

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- A mask. The concept of a mask is well known in lithography, and it includes mask types such as binary, alternating phase-shift, and attenuated phase-shift, as well as various hybrid mask types. Placement of such a mask in the radiation beam causes selective transmission (in the case of a transmissive mask) or reflection (in the case of a reflective mask) of the radiation impinging on the mask, according to the pattern on the mask. In the case of a mask, the support structure will generally be a mask table, which ensures that the mask can be held at a desired position in the incoming radiation beam, and that it can be moved relative to the beam if so desired.

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- A programmable mirror array. One example of such a device is a matrix-addressable surface having a viscoelastic control layer and a reflective surface. The basic principle behind such an apparatus is that (for example) addressed areas of the reflective surface reflect incident light as diffracted light, whereas unaddressed areas reflect incident

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light as undiffracted light. Using an appropriate filter, the said undiffracted light can be filtered out of the reflected beam, leaving only the diffracted light behind; in this manner, the beam becomes patterned according to the addressing pattern of the matrix-addressable surface. An alternative embodiment of a programmable mirror array employs a matrix

5 arrangement of tiny mirrors, each of which can be individually tilted about an axis by applying a suitable localized electric field, or by employing piezoelectric actuation means. Once again, the mirrors are matrix-addressable, such that addressed mirrors will reflect an incoming radiation beam in a different direction to unaddressed mirrors; in this manner, the reflected beam is patterned according to the addressing pattern of the matrix-addressable

10 mirrors. The required matrix addressing can be performed using suitable electronic means.

In both of the situations described hereabove, the patterning means can comprise one or more programmable mirror arrays. More information on mirror arrays as here referred to can be gleaned, for example, from United States Patents US 5,296,891 and US 5,523,193, and PCT patent applications WO 98/38597 and WO 98/33096, which are incorporated
15 herein by reference. In the case of a programmable mirror array, the said support structure may be embodied as a frame or table, for example, which may be fixed or movable as required.

- A programmable LCD array. An example of such a construction is given in United States Patent US 5,229,872, which is incorporated herein by reference. As above,
20 the support structure in this case may be embodied as a frame or table, for example, which may be fixed or movable as required.

For purposes of simplicity, the rest of this text may, at certain locations, specifically direct itself to examples involving a mask and mask table; however, the general principles discussed in such instances should be seen in the broader context of the
25 patterning means as hereabove set forth.

Lithographic projection apparatus can be used, for example, in the manufacture of integrated circuits (ICs). In such a case, the patterning means may generate a circuit pattern corresponding to an individual layer of the IC, and this pattern can be imaged onto a target portion (*e.g.* comprising one or more dies) on a substrate (silicon wafer) that has been
30 coated with a layer of radiation-sensitive material (resist). In general, a single wafer will contain a whole network of adjacent target portions that are successively irradiated via the

projection system, one at a time. In current apparatus, employing patterning by a mask on a mask table, a distinction can be made between two different types of machine. In one type of lithographic projection apparatus, each target portion is irradiated by exposing the entire mask pattern onto the target portion in one go; such an apparatus is commonly referred to as a wafer stepper. In an alternative apparatus — commonly referred to as a step-and-scan apparatus — each target portion is irradiated by progressively scanning the mask pattern under the projection beam in a given reference direction (the "scanning" direction) while synchronously scanning the substrate table parallel or anti-parallel to this direction; since, in general, the projection system will have a magnification factor M (generally < 1), the speed V at which the substrate table is scanned will be a factor M times that at which the mask table is scanned. More information with regard to lithographic devices as here described can be gleaned, for example, from US 6,046,792, incorporated herein by reference.

In a manufacturing process using a lithographic projection apparatus, a pattern (e.g. in a mask) is imaged onto a substrate that is at least partially covered by a layer of radiation-sensitive material (resist). Prior to this imaging step, the substrate may undergo various procedures, such as priming, resist coating and a soft bake. After exposure, the substrate may be subjected to other procedures, such as a post-exposure bake (PEB), development, a hard bake and measurement/inspection of the imaged features. This array of procedures is used as a basis to pattern an individual layer of a device, e.g. an IC. Such a patterned layer may then undergo various processes such as etching, ion-implantation (doping), metallization, oxidation, chemo-mechanical polishing, etc., all intended to finish off an individual layer. If several layers are required, then the whole procedure, or a variant thereof, will have to be repeated for each new layer. Eventually, an array of devices will be present on the substrate (wafer). These devices are then separated from one another by a technique such as dicing or sawing, whence the individual devices can be mounted on a carrier, connected to pins, etc. Further information regarding such processes can be obtained, for example, from the book "Microchip Fabrication: A Practical Guide to Semiconductor Processing", Third Edition, by Peter van Zant, McGraw Hill Publishing Co., 1997, ISBN 0-07-067250-4, incorporated herein by reference.

For the sake of simplicity, the projection system may hereinafter be referred to as the "lens"; however, this term should be broadly interpreted as encompassing various types of projection system, including refractive optics, reflective optics, and catadioptric systems, for example. The radiation system may also include components operating according to
5 any of these design types for directing, shaping or controlling the projection beam of radiation, and such components may also be referred to below, collectively or singularly, as a "lens". Further, the lithographic apparatus may be of a type having two or more substrate tables (and/or two or more mask tables). In such "multiple stage" devices the additional tables may be used in parallel, or preparatory steps may be carried out on one or more
10 tables while one or more other tables are being used for exposures. Dual stage lithographic apparatus are described, for example, in US 5,969,441 and WO 98/40791, incorporated herein by reference.

It has been proposed to immerse the substrate in a lithographic projection apparatus in a liquid having a relatively high refractive index, e.g. water, so as to fill the
15 space between the final optical element of the projection lens and the substrate. The point of this is to enable imaging of smaller features because the exposure radiation will have a shorter wavelength in the liquid than in air or in a vacuum. (The effect of the liquid may also be regarded as increasing the effective NA of the system).

However, submersing the substrate or substrate and substrate table in a bath of
20 liquid (see for example US 4,509,852, hereby incorporated in its entirety by reference) means that there is a large body of liquid that must be accelerated during a scanning exposure. This requires additional or more powerful motors and turbulence in the liquid may lead to undesirable and unpredictable effects.

One of the solutions proposed is for a liquid supply system to provide liquid on
25 only a localized area of the substrate and inbetween the final element of the projection system and the substrate (the substrate generally has a larger surface area than the final element of the projection system). One way which has been proposed to arrange for this is disclosed in WO 99/49504, hereby incorporated in its entirety by reference. As illustrated in Figures 19 and 20, liquid is supplied by at least one inlet IN onto the substrate,
30 preferably along the direction of movement of the substrate relative to the final element, and is removed by at least one outlet OUT after having passed under the projection system.

That is, as the substrate is scanned beneath the element in a $-X$ direction, liquid is supplied at the $+X$ side of the element and taken up at the $-X$ side. Figure 20 shows the arrangement schematically in which liquid is supplied via inlet IN and is taken up on the other side of the element by outlet OUT which is connected to a low pressure source. In the illustration of Figure 19 the liquid is supplied along the direction of movement of the substrate relative to the final element, though this does not need to be the case. Various orientations and numbers of in- and out-lets positioned around the final element are possible, one example is illustrated in Figure 20 in which four sets of an inlet with an outlet on either side are provided in a regular pattern around the final element.

Difficulties in large loss of liquid from the liquid supply system can arise with this system and any other systems that provide liquid on only a localized area of the substrate and between the final element of the projection system and the substrate when edge portions of the substrate are being imaged and the localised area crosses over the edge of the substrate.

It is an object of the present invention to provide a lithographic projection apparatus in which liquid loss from the supply system is minimized during exposure of an edge portion of the substrate.

This and other objects are achieved according to the invention in a lithographic apparatus as specified in the opening paragraph, characterized in that said substrate table further comprises an edge seal member for at least partly surrounding an edge of the object and for providing a primary surface facing said projection system substantially co-planar with a primary surface of the object, and in that the liquid supply system provides liquid to a localised area of said object and/or said edge seal member and/or substrate.

If the object is the substrate, the edge seal member is for surrounding a position on the substrate table where, in use, the substrate is to be placed e.g. surrounding the chuck or pimple table on which the substrate is held. In this way the substrate can be positioned closely adjacent to the edge of the edge seal member such that as an edge of the substrate moves under the projection lens there is no sudden loss of liquid from the space because there is no large gap for the liquid to flow through. The edge seal member may be an

integral part of the substrate table or may be moveably mounted relative to the remainder of the substrate table. In the latter case, it can be arranged such that the gap between the edge seal member and the object can be varied and/or the height of the primary surface of the edge seal member can be varied to accommodate variations in object height or thickness
5 i.e. to ensure that the primary surface of the edge seal member is substantially coplanar with the primary surface of the object. The object may also be a sensor e.g. a projection beam sensor.

Preferably the substrate table further comprises a gap seal member for abutting or partly overlapping, in the direction of the optical axis, both the edge seal member and the
10 object. For example, in this way the gap between the edge seal member and a substrate (as the object), which is due to the size mismatch between the inner edge of the edge seal member and the outer edge of the substrate (which is necessary to accommodate slight variations in the diameter of the substrate), can be covered by the gap seal member. This further reduces the amount of liquid loss into the gap between the edge seal member and
15 the substrate. Preferably the gap seal member is for being in contact with the primary surfaces, thereby spanning the gap between the edge seal member and the object.

If the gap seal member has inner and outer edges, at least one the of edges may be tapered such that the thickness of the gap seal member facing away from the edge seal member or the object decreases towards the edge of the gap seal member. This helps the
20 liquid supply system move smoothly over the gap between the object and the edge seal member.

One way to hold the gap seal member removably in place is to provide the substrate table with a vacuum port in the primary surface of said edge seal member.

Another way to minimise the amount of liquid which escapes into the gap between
25 the edge seal member and the object is to provide the substrate table with a hydrophobic layer facing edge portions of said edge seal member and object on an opposite side of the edge seal member and object to the projection system. Such a hydrophobic layer may be any material which exhibits hydrophobic properties, for example Teflon, silicon rubber or other plastics materials. Inorganic coatings are generally preferred because they have better
30 radiation resistance than organic coatings. Preferably the liquid has a contact angle of

greater than 90° with the hydrophobic layer. This reduces the chances of liquid seeping into the gap.

An alternative way of achieving the above mentioned objects is by providing a lithographic apparatus as specified in the opening paragraph, characterised in that said
5 substrate table further comprises an edge seal member for at least partly surrounding an edge of the object, and a further edge seal member for extending across the gap between said edge seal member and the object and for being in contact with the object.

In this way the gap between the edge seal member and the object is closed off so that there is no gap between the edge seal member and the object through which liquid
10 from the liquid supply system can pass. This is particularly so if the further edge seal member is flexible in which case a better seal between the further edge seal member and the object is achievable.

Preferably the flexible further edge seal member is attached to the edge seal member and has a port, connected to a vacuum source, adjacent its end distal from said
15 edge seal member, such that on actuation of said vacuum source, said flexible further edge seal member is deflectable upwards to contact against the object thereby to form a seal between said flexible further edge seal member and the object due to the force generated by the vacuum source acting on the object. This allows the flexible further edge seal member to be actuatable to contact with the object and to be deactuatable so that it falls away from
20 the object. The application of the vacuum ensures a good seal between the flexible further edge seal member and the object.

In an alternative embodiment the flexible further edge seal member is disposed between the edge seal member and the object and with a surface substantially co-planar with the primary surfaces of the edge seal member and the object. In this way the gap
25 between the edge seal member and the object can be sealed such that only small amounts of liquid can pass into the gap. Preferably the flexible further edge seal member is shaped for contacting the object on the surface opposite its primary surface and advantageously is effective to apply a force to the object away from the object table when the object is held on the object table. In this way, in particular if the object is the substrate, the flexible
30 further edge seal member can help in the removal of the substrate from the substrate table after exposure of the substrate.

An alternative way to address the problem of loss of liquid at edge portions of the object, in a lithographic apparatus as specified in the opening paragraph is to provide the substrate table with an edge seal member for at least partly surrounding an edge of the object, and a vacuum port or a liquid supply port positioned to provide a vacuum or liquid to the gap between said edge seal member and the object on a side opposite said projection system.

In the case of a liquid supply system, no liquid can find its way into the gap between the edge seal member and the object from the space between the projection lens and the object, because that gap is already filled with liquid. If the vacuum alternative is used, any liquid which does find its way into that gap will be removed and can be recycled. The provision of the vacuum supply is advantageous when a gas seal member of a liquid supply system is used to keep the liquid in the space between the projection lens and the object. This is because it can not only remove any liquid passing into the gap but also any gas from the gas seal member.

Further, a channel positioned radially inwardly of the vacuum port, the channel being connected to a gas source such that on actuation of the vacuum source a flow of gas radially outwardly from said channel toward said vacuum source is establishable, is advantageous. Such a flow of gas can be used to ensure that any liquid which does reach the non-immersed side of the object is caught in the gas flow and transported away towards the vacuum source.

Objects of the present invention may also be achieved according to the invention in a lithographic apparatus as specified in the opening paragraph, characterized in that said substrate table further comprises a support surface for supporting an intermediary plate between said projection system and the object and not in contact with the object.

In this way an intermediary plate can be used which is of an overall size larger than the object so that, for example, during imaging of edge portions of the object, the liquid supply system is situated at a medial portion of the intermediary plate such that no problems with loss of liquid through gaps at edges exist. With such a system it is also possible to provide the substrate table with a transmission image sensor (TIS) for sensing a beam and wherein the intermediary plate is positionable between the sensor and said projection system. Thus it is possible for the transmission image sensor to detect a beam

under the same conditions that a substrate is to be imaged. This is advantageous in that it will therefore be possible to more accurately position the substrate table so that the projection beam is correctly focussed on the substrate.

5 Object of the invention may also be achieved according to the invention in a lithographic apparatus as specified in the opening paragraph, characterised in further comprising a member of the liquid supply system extending along at least part of the boundary of said space between the final element of said projection system and said substrate table; and capillaries extending away from said substrate table and positioned between said member and said final element of said projection system.

10 In this way, a larger gap may be spanned over the edge of the object before catastrophic liquid loss occurs as capillary action aids in the liquid spanning gaps.

Preferably the inner coating of the capillary is hydrophobic and the apparatus comprises means for applying a potential difference between said liquid in said space and said capillaries. In this way, an even larger gap may be spanned for liquid loss.

15 According to a further aspect of the invention there is provided a device manufacturing method comprising the steps of:

- providing a substrate that is at least partially covered by a layer of radiation-sensitive material;
- providing a projection beam of radiation using a radiation system;
- 20 - using patterning means to endow the projection beam with a pattern in its cross-section;
- projecting the patterned beam of radiation onto a target portion of the layer of radiation-sensitive material,
- providing a liquid to at least partly fill the space between an object on the
- 25 substrate table and a final element of a projection system used in said step of projecting;

characterized either: by providing an edge seal member surrounding at least part of an edge of the object and with a primary surface substantially co-planar to a primary surface of the object wherein said liquid is provided to a localized area of said object and/or edge seal member, or

by providing an edge seal member at least partly surrounding an edge of the object and a further edge seal member extending across the gap between the edge seal member and the object in contact with the object, or

5 by providing an edge seal member at least partly surrounding an edge of the object and providing a vacuum or liquid to the gap between the edge seal member and the object on a side of the object opposite to said projection system, or

by positioning an intermediary plate in the space between the object and the final element of the projection system with liquid either side of it, or

10 in providing a member extending along at least part of the boundary of the space between the final element of the projection system and said substrate table and providing capillaries extending away from the substrate table between the member and the final element of the projection system.

Although specific reference may be made in this text to the use of the apparatus according to the invention in the manufacture of ICs, it should be explicitly understood that
15 such an apparatus has many other possible applications. For example, it may be employed in the manufacture of integrated optical systems, guidance and detection patterns for magnetic domain memories, liquid-crystal display panels, thin-film magnetic heads, etc. The skilled artisan will appreciate that, in the context of such alternative applications, any use of the terms "reticle", "wafer" or "die" in this text should be considered as being
20 replaced by the more general terms "mask", "substrate" and "target portion", respectively.

In the present document, the terms "radiation" and "beam" are used to encompass all types of electromagnetic radiation, including ultraviolet radiation (*e.g.* with a wavelength of 365, 248, 193, 157 or 126 nm).

25

Embodiments of the invention will now be described, by way of example only, with reference to the accompanying schematic drawings in which:

Figure 1 depicts a lithographic projection apparatus according to an embodiment of the invention;

30 Figure 2 depicts the liquid reservoir of the first embodiment of the invention;

Figure 3 is similar to Figure 2 showing an edge seal member on the substrate table according to an embodiment of the invention;

Figure 4 illustrates a second embodiment of the invention;

5 Figure 5 illustrates an alternative form of the second embodiment of the present invention;

Figure 6 illustrates a detail of the second embodiment of the present invention;

Figure 7 illustrates a third embodiment of the present invention;

Figure 8a illustrates a first version of a fourth embodiment of the present invention;

10 Figure 8b illustrates a second version of the fourth embodiment;

Figure 8c illustrates a third version of the fourth embodiment;

Figure 9 illustrates in detail further aspects of the first version of the fourth embodiment of the present invention;

Figure 10 illustrates a fifth embodiment of the present invention;

15 Figure 11 illustrates a sixth embodiment of the present invention;

Figure 12 illustrates in plan the substrate and edge seal member of a seventh embodiment of the present invention;

Figure 13 illustrates a cross section through the seventh embodiment of the present invention;

20 Figure 14 illustrates a detail of the seventh embodiment of the present invention;

Figure 15 illustrates in detail a further arrangement of the seventh embodiment;

Figure 16 illustrates an eighth embodiment of the present invention;

Figure 17 illustrates a ninth embodiment of the present invention;

Figure 18 illustrates a tenth embodiment of the present invention;

25 Figure 19 illustrates an alternative liquid supply system according to an embodiment of the invention; and

Figure 20 illustrates, in plan, the system of Figure 19.

In the Figures, corresponding reference symbols indicate corresponding parts.

Embodiment 1

Figure 1 schematically depicts a lithographic projection apparatus according to a particular embodiment of the invention. The apparatus comprises:

- a radiation system Ex, IL, for supplying a projection beam PB of radiation (*e.g.* DUV radiation), which in this particular case also comprises a radiation source LA;
 - a first object table (mask table) MT provided with a mask holder for holding a mask MA (*e.g.* a reticle), and connected to first positioning means for accurately positioning the mask with respect to item PL;
 - a second object table (substrate table) WT provided with a substrate holder for holding a substrate W (*e.g.* a resist-coated silicon wafer), and connected to second positioning means for accurately positioning the substrate with respect to item PL;
 - a projection system ("lens") PL (*e.g.* a refractive system) for imaging an irradiated portion of the mask MA onto a target portion C (*e.g.* comprising one or more dies) of the substrate W.
- As here depicted, the apparatus is of a transmissive type (*e.g.* has a transmissive mask). However, in general, it may also be of a reflective type, for example (*e.g.* with a reflective mask). Alternatively, the apparatus may employ another kind of patterning means, such as a programmable mirror array of a type as referred to above.

The source LA (*e.g.* an excimer laser) produces a beam of radiation. This beam is fed into an illumination system (illuminator) IL, either directly or after having traversed conditioning means, such as a beam expander Ex, for example. The illuminator IL may comprise adjusting means AM for setting the outer and/or inner radial extent (commonly referred to as σ -outer and σ -inner, respectively) of the intensity distribution in the beam. In addition, it will generally comprise various other components, such as an integrator IN and a condenser CO. In this way, the beam PB impinging on the mask MA has a desired uniformity and intensity distribution in its cross-section.

It should be noted with regard to Figure 1 that the source LA may be within the housing of the lithographic projection apparatus (as is often the case when the source LA is a mercury lamp, for example), but that it may also be remote from the lithographic projection apparatus, the radiation beam which it produces being led into the apparatus (*e.g.* with the aid of suitable directing mirrors); this latter scenario is often the case when

the source LA is an excimer laser. The current invention and Claims encompass both of these scenarios.

The beam PB subsequently intercepts the mask MA, which is held on a mask table MT. Having traversed the mask MA, the beam PB passes through the lens PL, which focuses the beam PB onto a target portion C of the substrate W. With the aid of the second positioning means (and interferometric measuring means IF), the substrate table WT can be moved accurately, *e.g.* so as to position different target portions C in the path of the beam PB. Similarly, the first positioning means can be used to accurately position the mask MA with respect to the path of the beam PB, *e.g.* after mechanical retrieval of the mask MA from a mask library, or during a scan. In general, movement of the object tables MT, WT will be realized with the aid of a long-stroke module (course positioning) and a short-stroke module (fine positioning), which are not explicitly depicted in Figure 1. However, in the case of a wafer stepper (as opposed to a step-and-scan apparatus) the mask table MT may just be connected to a short stroke actuator, or may be fixed.

The depicted apparatus can be used in two different modes:

1. In step mode, the mask table MT is kept essentially stationary, and an entire mask image is projected in one go (*i.e.* a single "flash") onto a target portion C. The substrate table WT is then shifted in the x and/or y directions so that a different target portion C can be irradiated by the beam PB;

2. In scan mode, essentially the same scenario applies, except that a given target portion C is not exposed in a single "flash". Instead, the mask table MT is movable in a given direction (the so-called "scan direction", *e.g.* the y direction) with a speed v , so that the projection beam PB is caused to scan over a mask image; concurrently, the substrate table WT is simultaneously moved in the same or opposite direction at a speed $V = Mv$, in which M is the magnification of the lens PL (typically, $M = 1/4$ or $1/5$). In this manner, a relatively large target portion C can be exposed, without having to compromise on resolution.

Figure 2 shows the liquid reservoir 10 between the projection system PL and the substrate W which is positioned on the substrate stage WT. The liquid reservoir 10 is filled with a liquid 11 having a relatively high refractive index, *e.g.* water, provided via inlet/outlet ducts 13. The liquid has the effect that the radiation of the projection beam is a

shorter wavelength in the liquid than in air or in a vacuum, allowing smaller features to be resolved. It is well known that the resolution limit of a projection system is determined, inter alia, by the wavelength of the projection beam and the numerical aperture of the system. The presence of the liquid may also be regarded as increasing the effective
5 numerical aperture. Furthermore, at fixed numerical aperture, the liquid is effective to increase the depth of field.

The reservoir 10 forms a preferably contactless seal to the substrate W around the image field of the projection lens PL so that the liquid is confined to fill the space between the substrate's primary surface, which faces the projection system PL, and the final optical
10 element of the projection system PL. The reservoir is formed by a seal member 12 positioned below and surrounding the final element of the projection lens PL. Thus, the liquid supply system provides liquid on only a localised area of the substrate. The seal member 12 forms part of the liquid supply system for filling the space between the final element of the projection system and the substrate with a liquid. This liquid is brought into
15 the space below the projection lens and within the seal member 12. The seal member 12 preferably extends a little above the bottom element of the projection lens and the liquid rises above the final element so that a buffer of liquid is provided. The seal member 12 has an inner periphery that at the upper end closely conforms to the shape of the projection system or the final elements thereof and may, e.g. be round. At the bottom the inner
20 periphery closely conforms to the shape of the image field, e.g. rectangular, though this is not necessarily so. The seal member is substantially stationary in the XY plane relative to the projection system though there may be some relative movement in the Z direction (in the direction of the optical axis). A seal is formed between the seal member and the surface of the substrate. This seal is preferably a contactless seal and may be a gas seal.

25 The liquid 11 is confined in the reservoir 10 by a seal device 16. As illustrated in Figure 2, the seal device is a contactless seal i.e. a gas seal. The gas seal is formed by gas, e.g. air or synthetic air, provided under pressure via inlet 15 to the gap between seal member 12 and substrate W and extracted by first outlet 14. The over pressure on the gas inlet 15, vacuum level or under pressure on the first outlet 14 and the geometry of the gap
30 are arranged so that there is a high-velocity air flow inwards towards the optical axis of the

apparatus that confines the liquid 11. As with any seal, some liquid is likely to escape, for example up the first outlet 14.

Figures 19 and 20 also depict a liquid reservoir defined by inlet(s) IN, outlet(s) OUT, the substrate W and the final element of projection lens PL. Like the liquid supply system of Figure 2 the liquid supply system illustrated in Figures 19 and 20, comprising inlet(s) IN and outlet(s) OUT, supplies liquid to the primary surface of the substrate in a localised area between the final element of the projection system and the substrate and can suffer from loss of liquid at the substrate edge.

Thus, as used herein for the embodiments, the liquid supply system can comprise that as described in relation to Figure 2 and Figures 19 and 20.

A problem with the liquid supply arrangement illustrated in Figures 2, 19 and 20 occurs when imaging edge portions of the substrate W. This is because when the substrate W edge is positioned underneath the projection system PL one of the constraining walls (the substrate W) of the liquid supply system (the bottom one as illustrated) is removed thereby allowing immersion liquid to escape.

Figure 3 illustrates how the edge portion of a substrate W may be imaged without catastrophic loss of immersion liquid from the liquid supply system. This is achieved by the provision of a cover plate or edge seal member 17 on the substrate table WT. The edge seal member 17 has an upper (as illustrated) primary surface substantially co-planar with the upper primary surface of substrate W and is closely adjacent to the edge of the substrate W so that there is no sudden loss of liquid as the edge of the substrate moves under the projection lens PL. Some liquid loss into the gap may still occur. Of course there are arrangements in which the whole construction illustrated in Figures 2 and 3 is positioned upside down so that it is the lower surfaces of the edge seal member and the substrate which face the projection system and which are substantially co-planar. The surfaces are therefore referred to as the primary surfaces which face the projection system PL rather than upper surfaces. References herein to upper surfaces and lower surfaces may be also appropriately considered as references to lower and upper surfaces respectively in an upside-down configuration.

With this system, the liquid supply system (e.g. reservoir 10) can be positioned over the edge of the substrate W and can even be moved completely off the substrate W. This enables edge portions of the substrate W to be imaged.

The edge seal member 17 may form an integral part of the substrate table WT (as illustrated in Figure 4 as edge seal member 117) or may be temporarily mounted relative to the remainder of the substrate table by the use of, for example, vacuum suction or through use of electromagnetic forces. Preferably the edge seal member 17 is moveable relative to the remainder of the substrate table (as illustrated in Figures 5 and 6) such that the height above the substrate table WT of the primary surface of the edge seal member 17 may be adjusted such that it is substantially co-planar with the primary surface of the substrate W. In this way the same edge seal member 17 may be used for different thicknesses of substrate W (thickness tolerance is about 25 μ m though the embodiment can account for up to about 0.2mm variation). The positioning mechanism for the edge seal member 17 may be through use of piezoelectric elements or electromagnetism, worm gear etc. A suitable mechanism is described in relation to the second embodiment described below.

The edge seal member 17 may be formed of several individual segments, each of which surrounds a portion of the edge of the substrate W.

Embodiment 2

The second embodiment is illustrated in Figures 4 to 6 and is the same or similar as the first embodiment except as described below.

In the embodiment of Figures 4 and 5 an edge liquid supply system provides liquid to a reservoir 30 via a port 40. The liquid in the reservoir 30 is optionally the same as the immersion liquid in the liquid supply system. The reservoir 30 is positioned on the opposite side of the substrate W to the projection lens and adjacent the edge of the substrate W and the edge of the edge seal member 17, 117. In Figure 5, the edge seal member 17 is comprised of an element which is separate to the substrate table WT whereas in Figure 4 the edge seal member 117 is provided by an integral portion of the substrate table WT. As can be seen most clearly from Figure 4, the substrate W is supported on the substrate table WT by a so-called pimple table 20. The pimple table 20 comprises a plurality of projections on which the substrate W rests. The substrate W is held in place

by, e.g., a vacuum source sucking the substrate onto the top surface of the substrate table WT. With the use of the reservoir 30, when the edge of the substrate W is being imaged, (i.e. when liquid in the liquid supply system under the projection lens traverses across an edge of the substrate), liquid cannot escape from the liquid supply system into the gap
5 between the edge seal member 17, 117 and the substrate W because that space is already filled with liquid.

The mechanism 170 shown in Figure 5 for moving the edge seal member 17 relative to the remainder of the substrate table WT is illustrated in detail in Figure 6. The reason for moving the edge seal member 17 in this way is so that its primary surface can be
10 made to be substantially co-planar with the primary surface of the substrate W. This allows a smooth movement of the liquid supply system over edge portions of the substrate W so that the bottom inner periphery of the liquid supply system can be moved to positions partly on the primary surface of substrate W and partly on the primary surface of the edge seal member 17.

15 A level sensor (not illustrated) is used to detect the relative heights of the primary surfaces of the substrate W and the edge seal member 17. Based on the results of the level sensor, control signals are sent to the actuator 171 in order to adjust the height of the primary surface of the edge seal member 17. A closed loop actuator could also be used for this purpose.

20 The actuator 171 is a rotating motor which rotates a shaft 176. The shaft 176 is connected to a circular disc at the end distal to the motor 171. The shaft 176 is connected away from the centre of the disc. The disc is located in a circular recess in a wedge portion 172. Ball bearings may be used to reduce the amount of friction between the circular disc and the sides of the recess in the wedge portion 172. The motor 171 is held in place by leaf
25 springs 177. On actuation of the motor the wedge portion is driven to the left and right as illustrated (i.e. in the direction of the slope of the wedge portion) because of the excentre position of the shaft 176 in the disc. The motor is prevented from moving in the same direction as the direction of movement of the wedge portion 172 by the springs 177.

30 As the wedge portion 172 moves left and right as illustrated in Figure 6, its top surface 175 (which is the surface of the wedge which is sloped in relation to the primary surface of the edge seal member 17) contacts the bottom sloped surface of a further wedge

member 173 which is fixed to the bottom of the edge seal member 17. The edge seal member 17 is prevented from moving in the direction of movement of the wedge member 172 so that when the wedge member 172 moves left and right the edge seal member 17 is lowered and raised respectively. Some biasing of the edge seal member 17 towards the substrate table WT may be necessary.

Obviously the further wedge member 173 could be replaced by an alternative shape, for example a rod positioned perpendicularly to the direction of movement of the wedge 172. If the coefficient of friction between the wedge member 172 and the further wedge member 173 is greater than the tangent of the wedge angle then the actuator 170 is self-braking meaning that no force is required on the wedge member 172 to hold it in place. This is advantageous as the system will then be stable when the actuator 171 is not actuated. The accuracy of the mechanism 170 is of the order of a few μm .

Especially in the case of the edge seal member 117 being an integral part of the substrate table WT, a mechanism may be provided to adjust the height of the substrate W or the member supporting the substrate W so that the primary surfaces of the edge seal member 17, 117 and the substrate can be made substantially co-planar.

Embodiment 3

The third embodiment is illustrated in Figure 7 and is the same or similar as the first embodiment except as described below.

This embodiment is described in relation to an edge seal member 117 which is an integral part of the substrate table WT. However, this embodiment is equally applicable to an edge seal member 17 which is movable relative to the substrate table WT. A vacuum port 46 connected to a vacuum source is provided adjacent edge portions of the edge seal member 117 and the substrate W on the opposite side of the substrate W to the projection system. In its simplest form the embodiment may work only with that vacuum supply via port 46. However, the basic idea can be improved by the provision of a substrate table WT as illustrated in detail in Figure 7.

A portion 48 of the substrate table WT extends from the edge of the edge seal portion 117 radially inwardly so that it is positioned below the substrate table W on the other side of the substrate W to the projection system. Any immersion liquid which leaks

through the gap between the portion 48 and the substrate W is attracted towards the vacuum source via port 46. A channel 42 is provided radially inwardly of the vacuum source also under the substrate W and is connected to a gas source. This may be a gas at a pressure greater than atmospheric pressure or it may be that the channel 42 is simply open to the atmosphere. This creates a flow of air radially outwardly below the substrate W between the portion 48 of substrate table WT below the substrate W and the pimple table 20. With this flow of air any liquid escaping between edge seal member 117 and the substrate W is pulled towards an annular compartment 44 in fluid connection with the vacuum source. The compartment 44 is positioned between an annular port 47 open to the gap and the port 46 connected to the vacuum source. The compartment helps in establishing uniform flow. The channel 42 is connected to a continuous annular groove (shown as a widening of the duct). The compartment 44, port 47, and/or the groove of channel 42 need not be annular and can be other appropriate shapes or configurations.

In one working embodiment, the gap between the portion 48 of substrate table WT and the substrate W is of the order of up to 100 μm (though the gap may not exist i.e. is zero), which prevents a high flow rate of liquid through the gap due to capillary action. The height of the portion 45 of the substrate table WT between the groove connected to channel 42 and compartment 44 is such that the distance between the bottom of the substrate W and the top of that portion 45 (indicated as distance D1 in Figure 7) is typically of the order of 100 μm and is chosen such that a uniform gas flow of in the region of at least 1 m/s is achievable with a pressure loss of less than 0.5 bar. Such an arrangement ensures that only very little, if any, liquid passes through the gap D1 and interferes with the pimple table 20. Other values will also work.

Embodiment 4

The fourth embodiment is illustrated in Figures 8 and 9 and is the same or similar as the first embodiment except as described below.

This embodiment is described in relation to an edge seal member 117 which is an integral part of the substrate table WT. However, this embodiment is equally applicable to an edge seal member 17 which is movable relative to the substrate table WT.

In a first version of this embodiment as illustrated in Figure 8a, a further edge seal member 500 is used to bridge the gap between the edge seal member 117 and the substrate W. The further edge seal member is affixed to the edge seal member 117. The further edge seal member 500 is removably attachable against the surface of the substrate W opposite the primary surface. In this embodiment the further edge seal member 500 can be a flexible edge seal member which is actuatable to contact the under surface of the substrate W. When the flexible edge seal member 500 is deactivated it falls away from the substrate under gravity. The way this is achieved is illustrated in Figure 9 and is described below.

10 It is likely that the further edge seal member 500 will not prevent all of the immersion liquid from the liquid supply system from entering the space under the substrate W and for this reason a port 46 connected to a low pressure source may be provided under the substrate W adjacent edges of the edge seal member 117 and the substrate W in some or all of the versions of this embodiment. Of course the design of the area under the
15 substrate could be the same as that of the third embodiment.

A second version of this embodiment is illustrated in Figure 8b. Two further edge seal members 500a, 500b are used. The first of these edge seal members 500a is the same as in the first version. The second of these edge seal members 500b is affixed to the substrate table 20 i.e. underneath the substrate W and extends with its free end radially
20 outwardly from its attachment point. The second further edge seal member 500b clamps the first further edge seal member 500a against the substrate W. Compressed gas can be used to deform or move the second further edge seal member 500b.

A third version of this embodiment is shown in Figure 8c. The third version is the same as the second version except the first further edge seal member 500c clamps the
25 second further edge seal member 500d to the substrate W. This avoids, for example, the need for the compressed gas of the second version.

It will be appreciated that the embodiment will also work with only the second further edge seal member 500b, 500d with or without connection to vacuum.

Various ways of deforming the further edge seal members 500, 500a, 500b, 500c,
30 500d will now be described in relation to the first version of the embodiment.

As can be seen from Figure 9, a channel 510 is formed in the elongate direction of a flexible further edge seal member 500 (which preferably is an annular ring) and (a) discreet port(s) are provided in an upper surface of the flexible further edge seal member which faces the projection system and the underside of the substrate W. By connecting a vacuum source 515 to the duct 510 the flexible further edge seal member can be made to abut the substrate W by suction. When the vacuum source 515 is disconnected or switched off, the flexible further edge seal member 500 drops under gravity and/or pressure from port 46 to assume the position shown in dotted lines in Figure 9.

In an alternative embodiment a flexible further edge seal member 500 is formed with a mechanical pre-load such that it contacts the substrate W when the substrate is placed on the pimple table 20 and the flexible further edge seal member 500 deforms elastically so that it applies a force upwards on the substrate W to thereby make a seal.

In a further alternative, a flexible further edge seal member 500 may be forced against the substrate W by an overpressure generated by pressurised gas on port 46.

A flexible further edge seal member 500 may be fashioned from any flexible, radiation and immersion liquid resistant, non-contaminating material, for example, steel, glass e.g. Al_2O_3 , ceramic material e.g. SiC, Silicon, Teflon, low expansion glasses (e.g. Zerodur (TM) or ULE (TM)), carbon fibre epoxy or quartz and is typically between 10 and 500 μm thick, preferably between 30 and 200 μm or 50 to 150 μm in the case of glass. With a flexible further edge seal member 500 of this material and these dimensions, the typical pressure which is required to be applied to the duct 510 is approximately 0.1 to 0.6 bar.

Embodiment 5

The fifth embodiment is illustrated in Figure 10 and is the same or similar as the first embodiment except as described below.

This embodiment is described in relation to an edge seal member 117 which is an integral part of the substrate table WT. However, this embodiment is equally applicable to an edge seal member 17 which is movable relative to the substrate table WT.

In the fifth embodiment the gap between the edge seal member 117 and the substrate W is filled with a further edge seal member 50. The further edge seal member is

a flexible further edge seal member 50 which has a top surface which is substantially coplanar with the primary surfaces of the substrate W and the edge seal member 117. The flexible further edge seal member 50 is made of a compliant material so that minor variations in the diameter of substrate W and in the thickness of the substrate W can be accommodated by deflections of the flexible further edge seal member 50. When liquid in the liquid supply system under the projection lens passes over the edge of the substrate, the liquid cannot escape between the substrate W, flexible further edge seal member 50 and edge seal member 117 because the edges of those elements are tight against one another. Furthermore, because the primary surfaces of the substrate W and the edge seal member 117 and the top surface of the flexible further edge seal member 50 are substantially coplanar, the liquid supply system operation is not upset when it passes over the edge of the substrate W so that disturbance forces are not generated in the liquid supply system.

As can be seen from Figure 10, the flexible further edge seal member 50 is in contact with a surface of the substrate W opposite the primary surface of the substrate W, at an edge portion. This contact has two functions. First the fluid seal between the flexible further edge seal member 50 and the substrate W is improved. Second, the flexible further edge seal member 50 applies a force on the substrate W in a direction away from the pimple table 20. When the substrate W is held on the substrate table WT by, e.g. vacuum suction, the substrate can be held securely on the substrate table. However, when the vacuum source is switched off or disconnected, the force produced by the flexible further edge seal member 50 on the substrate W is effective to push the substrate W off the substrate table WT thereby aiding loading and unloading of substrates W.

The flexible further edge seal member 50 is made of a radiation and immersion liquid resistant material such as PTFE.

Embodiment 6

Figure 11 illustrates a sixth embodiment of the present invention which is the same or similar as the first embodiment except as described below.

This embodiment is described in relation to an edge seal member 117 which is an integral part of the substrate table WT. However, this embodiment is equally applicable to an edge seal member 17 which is movable relative to the substrate table WT.

The sixth embodiment illustrates how the pimple table 20 can be decoupled from the liquid supply system between the substrate W and the edge seal member 117. This is done by positioning an opening exposed to the atmosphere 65 between the edge of the substrate W and the vacuum holding the substrate W on the substrate table WT and
5 associated with the pimple table 20.

A layer 60, positioned on the opposite side of the substrate W to the projection system and under the substrate at its edge leaving a gap between the substrate W and the layer 60 of about 10 μm , is comprised of any material which is hydrophobic such as Teflon (TM), silicon rubber, or other plastics material. Inorganic materials are preferred because
10 they have better radiation resistance. In this way, liquid which finds its way into the gap between the substrate W and the edge seal member 117 when the liquid supply system is positioned over the edge of the substrate W is repelled such that an effective seal is formed and liquid does not find its way to the pimple table 20. Preferably, the immersion liquid has a contact angle of at least 90° with the hydrophobic layer 60.

15

Embodiment 7

A seventh embodiment of the present invention will be described with reference to Figures 12 to 15. The seventh embodiment is the same or similar as the first embodiment except as described below.

20

This embodiment is described in relation to an edge seal member 117 which is an integral part of the substrate table WT. However, this embodiment is equally applicable to an edge seal member 17 which is movable relative to the substrate table WT.

25

In the seventh embodiment, as is illustrated in Figure 12, the edge seal member 17 is annular with a central hole larger than the diameter of the circular substrate W. The shapes of the substrate W and edge seal member 17 may change so long as the central hole of the edge seal member 17 is larger than the outer diameter of the substrate W. In this way, the edge seal member 17 may accommodate variations in the substrate W diameter.

30

The edge seal member 17 is movable on the substrate table WT such that when the liquid supply system towards an edge portion of the substrate W in order to expose it, the edge seal member 17 can be moved closely to abut that edge portion of the substrate W

which is to be exposed. This is best illustrated in Figure 13 where the left hand side of the substrate W is about to be exposed.

As is clearly illustrated in Figure 14, the edge seal member 17 is movable both in the plane of the primary surface of the substrate W and preferably also in the Z direction (i.e. in the direction of the optical axis of the apparatus). In this way, the edge seal member 17 can be moved to the edge of the substrate W when required and can have the height of its top (primary) surface adjusted so that its primary surface is closely co-planar with the primary surface of the substrate W. This allows the liquid supply system to effectively contain the immersion liquid in its reservoir even when the edge of the substrate W is being imaged.

Also illustrated in Figure 14 is a projection 175 which has a top surface which is co-planar with the primary surface of the edge seal member 17, i.e. the primary surface of the edge seal member 17 overhangs on an edge adjacent the substrate W so that the projection extends towards the optical axis of the apparatus. As can be seen from Figure 14, this allows the gap between the primary surfaces of the substrate W and edge seal member 17 to be minimised even when the edge of the substrate W is slightly curved (i.e. the edge of the substrate W is not perpendicular to the primary surface).

Another way of improving or reducing the gap between the edge seal member 17 and the substrate W is to provide a further (flexible) edge seal member 177 between the edge of the edge seal member 17 closest to the substrate W and the substrate W. This is illustrated in Figure 15. This may be done with or without a projection 175. A further flexible edge seal member 177 can deform around the edge of the substrate W so as to form a tight seal with the substrate W. The further flexible edge seal member 177 is attached to the edge seal member 17. The further flexible edge seal member 177 has an upper surface which is substantially co-planar with the primary surfaces of the substrate W and the edge seal member 17.

Embodiment 8

Figure 16 illustrates an eighth embodiment of the present invention which is the same or similar as the first embodiment except as described below.

This embodiment is described in relation to an edge seal member 117 which is an integral part of the substrate table WT. However, this embodiment is equally applicable to an edge seal member 17 which is movable relative to the substrate table WT.

As can be seen from Figure 16, the eighth embodiment includes a further edge seal member 100 for bridging the gap between the edge seal member 117 and the substrate W. In this case the further edge seal member 100 is a gap seal member which is positioned on the primary surfaces of the substrate W and the edge seal member 117 to span the gap between the substrate W and edge seal member 117. Thus, if the substrate W is circular, the gap seal member 100 will also be circular (annular).

The gap seal member 100 may be held in place by the application of a vacuum 105 to its underside (that is a vacuum source exposed through a vacuum port on the primary surface of the edge seal member 117). The liquid supply system can pass over the edge of the substrate W without the loss of liquid because the gap between the substrate W and the edge seal member 117 is covered over by the gap seal means 100. The gap seal member 100 can be put in place and removed by the substrate handler so that standard substrates and substrate handling can be used. Alternatively the gap seal member 100 can be kept at the projection system PL and put in place and removed by appropriate mechanisms (e.g. a substrate handling robot). The gap seal member 100 should be stiff enough to avoid deformation by the vacuum source. Advantageously the gap seal member 100 is less than 50, preferably 30 or 20 or even 10 μm thick to avoid contact with the liquid supply system, but should be made as thin as possible

The gap seal member 100 is advantageously provided with tapered edges 110 in which the thickness of the gap seal member 100 decreases towards the edges. This gradual transition to the full thickness of the gap seal member ensures that disturbance of the liquid supply system is reduced when it passes on top of the gap seal member 100.

Embodiment 9

The ninth embodiment will be described with reference to Figure 17. The solution shown in Figure 17 bypasses some of the problems associated with imaging edge portions of the substrate W as well as allows a transmission image sensor (TIS) 220 to be illuminated by the projection lens PL under the same conditions as the substrate W.

The ninth embodiment uses the liquid supply system described with respect to the first embodiment. However, rather than confining the immersion liquid in the liquid supply system under the projection lens on its lower side with the substrate W, the liquid is confined by an intermediary plate 210 which is positioned between the liquid supply system and the substrate W. The spaces 222, 215 between the intermediary plate 210 and the TIS 220 and the substrate W are also filled with liquid 111. This may either be done by two separate space liquid supply systems via respective ports 230, 240 as illustrated or by the same space liquid supply system via ports 230, 240. Thus the space 215 between the substrate W and the intermediary plate 210 and the space 220 between the transmission image sensor 220 and the intermediary plate 210 are both filled with liquid and both the substrate W and the transmission image sensor can be illuminated under the same conditions. Portions 200 provide a support surface or surfaces for the intermediary plate 210 which may be held in place by vacuum sources.

The intermediary plate 210 is made of such a size that it covers all of the substrate W as well as the transmission image sensor 220. Therefore, no edges need to be traversed by the liquid supply system even when the edge of the substrate W is imaged or when the transmission image sensor is positioned under the projection lens PL. The top surface of the transmission image sensor 220 and the substrate W are substantially co-planar.

The intermediate plate 210 can be removable. It can, for example, be put in place and removed by a substrate handling robot or other appropriate mechanism.

Embodiment 10

Figure 18 shows a modification of the liquid supply system which is applicable to any other embodiment described herein which is effective to increase the size of gap the immersion liquid can span before sudden liquid loss.

A plurality of capillaries 600 are provided between the liquid supply system (e.g. seal member 12) and the projection lens PL. These capillaries extend generally upwardly, *i.e.* away from the substrate W. If the capillaries have a radius r , the liquid film thickness h , which can be supported by the capillary, is given by the formula:

$$h = \frac{2\sigma \cos \theta}{rg\rho}$$

where σ is the interfacial tension, θ the contact angle between the liquid and the capillaries W and ρ the liquid density. Thus by making $\cos\theta$ positive (i.e. making the inner surface of the capillaries hydrophobic, for example by coating) the capillaries can support a portion of liquid with height h above the gap so that a larger gap can be spanned.

5 By applying a voltage between the hydrophobic coated capillaries and the liquid, $\cos\theta$ can be reduced to around zero and this allows free flow of liquid through the capillaries 600 (according to equation 1 above) so that liquid can be removed from the liquid supply system under the projection lens in little time by keeping the length of the capillaries low. This is advantageous for keeping the liquid clean. When the edge of the
10 substrate W is imaged, the voltage can be removed so that the gap can be spanned. In order to lift the liquid film from the substrate W, it is proposed to coat the substrate W edges with a hydrophobic material (or the resist on the substrate W edges can be removed as the substrate material itself is hydrophobic).

The capillaries 600 may be provided by substantially straight ducts with a
15 substantially circular cross-section or by other shaped ducts. For example, the capillaries may be made up of voids in a porous material.

All of the above described embodiments may be used to seal around the edge of the substrate W. Other objects on the substrate table WT may also need to be sealed in a similar way, such as sensors including sensors and/or marks which are illuminated with the
20 projection beam through the liquid such as the transmission image sensors, integrated lens interferometer and scanner (wavefront sensor) and spot sensor plates. Such objects may also include sensors and/or marks which are illuminated with non-projection radiation beams such as levelling and alignment sensors and/or marks. The liquid supply system may supply liquid to cover all of the object in such a case. Any of the above embodiments
25 may be used for this purpose. In some instances, the object will not need to be removed from the substrate table WT as, in contrast to the substrate W, the sensors do not need to be removed from the substrate table WT. In such a case the above embodiments may be modified as appropriate (e.g. the seals may not need to be moveable).

Each of the embodiments may be combined with one or more of the other
30 embodiments as appropriate. Further, each of the embodiments (and any appropriate combination of embodiments) can be applied simply to the liquid supply system of Figure

2 and Figures 19 and 20 without the edge seal member 17, 117 as feasible and/or appropriate.

Whilst specific embodiments of the invention have been described above, it will be appreciated that the invention may be practiced otherwise than as described. In particular, the invention is also applicable to other types of liquid supply systems, especially localised liquid area systems. If the seal member solution is used, it may be one in which a seal other than a gas seal is used. The description is not intended to limit the invention.

CLAIMS

1. A lithographic projection apparatus comprising:
- a radiation system for providing a projection beam of radiation;
 - 5 - a support structure for supporting patterning means, the patterning means serving to pattern the projection beam according to a desired pattern;
 - a substrate table for holding a substrate;
 - a projection system for projecting the patterned beam onto a target portion of the substrate; and
 - 10 - a liquid supply system for at least partly filling the space between the final element of said projection system and an object positioned on the substrate table, with liquid,

characterized in that said substrate table further comprises an edge seal member for at least partly surrounding an edge of the object and for providing a primary surface
15 facing said projection system substantially co-planar with a primary surface of the object and in that said liquid supply system provides liquid to a localised area of said object and/or said edge seal member and/or substrate.

2. An apparatus according to claim 1, wherein said edge seal member and
20 object are moveably mounted relative to one another.

3. An apparatus according to claim 1 or 2, wherein said edge seal member is moveable in a plane substantially parallel to said primary surface of said edge seal member for varying the distance between said edge seal member and the object.

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4. An apparatus according to claim 1, 2 or 3, wherein said substrate table further comprises an actuator for moving said edge seal member relative to the remainder of said substrate table in a direction substantially parallel to the optical axis of the apparatus.

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5 5. An apparatus according to claim 4, wherein said actuator comprises a wedge member which, on movement in a direction substantially parallel to said primary surface of said edge seal member, is effective to move said edge seal member relative to the remainder of said substrate table in the direction substantially parallel to the optical axis of the apparatus.

10 6. An apparatus according to claim 5, wherein said wedge is arranged to lock in place on removal of an actuation force by virtue of the coefficient of friction of said wedge.

15 7. An apparatus according to any one of the preceding claims, wherein said substrate table further comprises a hydrophobic layer adjacent edge portions of said edge seal member and the object on an opposite side of said edge seal member and the object to said projection system.

20 8. An apparatus according to claim 7, wherein said liquid has a contact angle of greater than 90° with said hydrophobic layer.

25 9. An apparatus according to any one of the preceding claims, wherein said edge seal member has a protrusion with a top surface co-planar with the primary surface of said edge seal member and extending towards the optical axis of said apparatus.

30 10. An apparatus according to any one of the preceding claims, wherein said substrate table further comprises a gap seal member for abutting or at least partly overlapping, in the direction of the optical axis, both said edge seal member and the object.

35 11. An apparatus according to claim 10 wherein said gap seal member is for being in contact with said primary surfaces thereby spanning a gap between said edge seal member and the object.

12. An apparatus according to claim 10 or 11, wherein said gap seal member has inner and outer edges at least one of which edges is tapered such that the distance of the surface of the gap seal member facing away from the primary surface of the edge seal member or the object decreases towards the edge of the gap seal member.

5

13. An apparatus according to any one of claims 10 to 12, wherein said substrate table further comprises a vacuum port in said primary surface of said edge seal member for holding said gap seal member in place.

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14. An apparatus according to any one of the preceding claims, wherein said substrate table includes means for varying the distance of the primary surface of said object relative to the remainder of said substrate table.

15

15. A lithographic projection apparatus comprising:

- a radiation system for providing a projection beam of radiation;
- a support structure for supporting patterning means, the patterning means serving to pattern the projection beam according to a desired pattern;
- a substrate table for holding a substrate;
- a projection system for projecting the patterned beam onto a target

20

portion of the substrate; and

- a liquid supply system for at least partly filling the space between the final element of said projection system and an object positioned on the substrate table, with liquid,

25

characterized in that said substrate table further comprises an edge seal member for at least partly surrounding an edge of the object, and a further edge seal member for extending across the gap between said edge seal member and the object and for being in contact with the object.

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16. An apparatus according to claim 15, wherein said further edge seal member is flexible.

17. An apparatus according to claim 16, wherein said flexible further edge seal member is attached to said edge seal member.

18. An apparatus according to claim 15, 16 or 17, wherein said flexible further edge seal member has a port, connected to a vacuum source, adjacent its end distal from said edge seal member, such that on actuation of said vacuum source, said flexible further edge seal member is deflectable upwards to contact against the object thereby to form a seal between said flexible further edge seal member and the object due to the force generated by the vacuum source acting on the object.

19. An apparatus according to claim 15 or 16, further comprising a second flexible further edge seal member attached under said object to said substrate table and with a free end radially outwardly from the attachment point.

20. An apparatus according to claim 16 or 17, wherein said flexible further edge seal member is disposed between said edge seal member and the object and with a surface substantially co-planar with said primary surfaces of said edge seal member and the object.

21. An apparatus according to claim 20, wherein said flexible further edge seal member is shaped for contacting the object on a surface opposite its primary surface.

22. An apparatus according to claim 20 or 21, wherein said flexible further edge seal member is effective to apply a force to the object away from said substrate table when the object is held on said substrate table.

23. A lithographic projection apparatus comprising:

- a radiation system for providing a projection beam of radiation;
- a support structure for supporting patterning means, the patterning means serving to pattern the projection beam according to a desired pattern;
- a substrate table for holding a substrate;

- a projection system for projecting the patterned beam onto a target portion of the substrate; and

- a liquid supply system for at least partly filling the space between the final element of said projection system and an object positioned on the substrate table, with
5 liquid,

characterized in that said substrate table further comprises an edge seal member for at least partly surrounding an edge of the object, and a vacuum port or a liquid supply port positioned to provide a vacuum or liquid to the gap between said edge seal member and the object on a side opposite said projection system.

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24. An apparatus according to claim 23, wherein said substrate table further comprises a channel positioned radially inwardly of said vacuum port, said channel being connected to a gas source such that on actuation of said vacuum source a flow of gas radially outwardly from said channel towards said vacuum source is establishable.

15

25. An apparatus according to claim 22 or 23, further comprising a compartment in said substrate table in fluid connection with said gap via said vacuum port and with said vacuum source.

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26. An apparatus according to claim 22, 23 or 24, wherein said substrate table further comprises a portion which extends below the object and is radially outwardly of said vacuum port.

25

27. A lithographic projection apparatus comprising:

- a radiation system for providing a projection beam of radiation;
- a support structure for supporting patterning means, the patterning means serving to pattern the projection beam according to a desired pattern;
- a substrate table for holding a substrate;
- a projection system for projecting the patterned beam onto a target
30 portion of the substrate; and

- a liquid supply system for filling the space between the final element of said projection system and an object positioned on said substrate table, with liquid;

characterized in that said substrate table further comprises a support surface for supporting an intermediary plate between said projection system and the object and not in contact with the object.

28. An apparatus according to claim 27, wherein said liquid supply system includes a liquid supply port for filling the space between said intermediary plate and said object with a liquid.

29. An apparatus according to claim 27 or 28, wherein said substrate table further comprises a transmission image sensor for sensing a beam and wherein said intermediary plate is positionable between said sensor and said projection system.

30. An apparatus according to claim 27, 28 or 29, wherein said liquid supply system includes a projection system liquid supply system for filling the space between the final element of said projection system and said intermediary plate with a liquid.

31. An apparatus according to any one of claims 27 to 30, wherein said intermediary plate has a cross sectional area in a plane perpendicular to the optical axis of the apparatus greater than that of said object such that all the edges of said object can be covered by said intermediary plate.

32. A lithographic projection apparatus comprising:

- a radiation system for providing a projection beam of radiation;
- a support structure for supporting patterning means, the patterning means serving to pattern the projection beam according to a desired pattern;
- a substrate table for holding a substrate;
- a projection system for projecting the patterned beam onto a target portion of the substrate; and

- a liquid supply system for at least partly filling the space between the final element of said projection system and an object positioned on said substrate table, with liquid;

characterized in further comprising:

5 - a member of the liquid supply system extending along at least part of the boundary of said space between the final element of said projection system and said substrate table; and

- capillaries extending away from said substrate table and positioned between said member and said final element of said projection system.

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33. Apparatus according to claim 32, wherein said capillaries are tubes.

34. Apparatus according to claim 32, wherein said capillaries are formed by a porous membrane.

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35. Apparatus according to any one of claims 32 to 34, wherein an inner coating of said capillaries is hydrophobic.

20 36. Apparatus according to any one of claims 32 to 35, further comprising means for applying a potential difference between said liquid in said space and said capillaries.

25 37. Apparatus according to any one of the preceding claims, wherein said object to be imaged is the substrate or a sensor.

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ABSTRACT**Lithographic Apparatus and Device Manufacturing Method**

5 A lithographic projection apparatus is disclosed in which the space between the final element of the projection system and the substrate is filled with a liquid. An edge seal member 17, 117 at least partly surrounds the substrate W or other object on the substrate table WT to prevent catastrophic liquid loss when edge portions of the substrate or are imaged or illuminated.

10

Fig. 3

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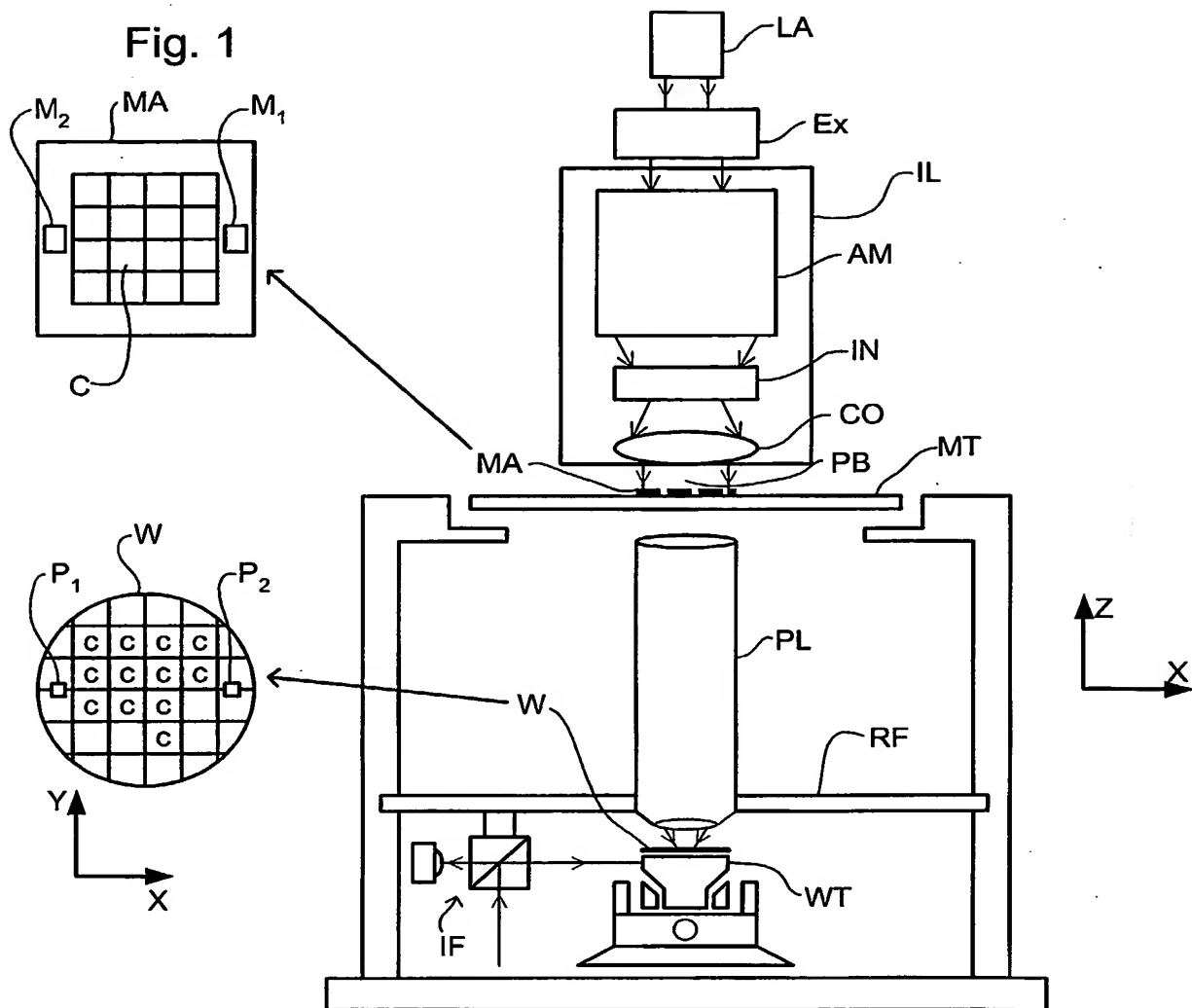


Fig. 2

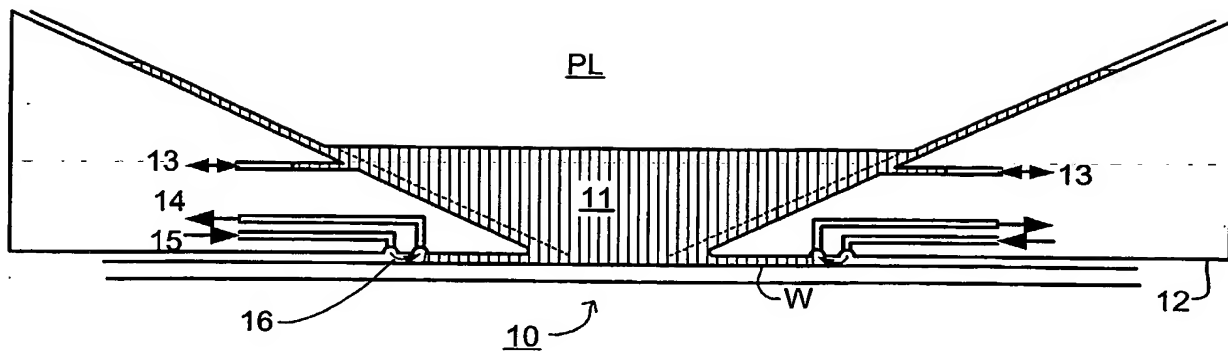


Fig. 3

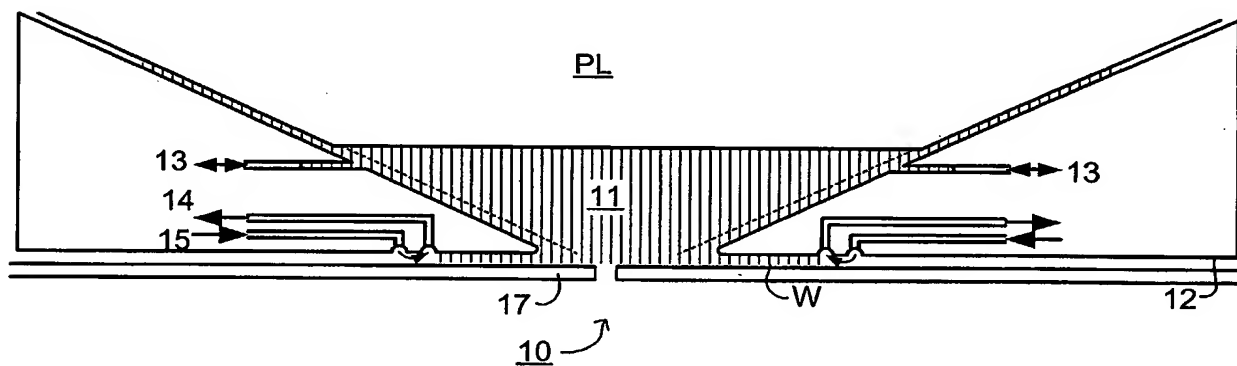


Fig. 4

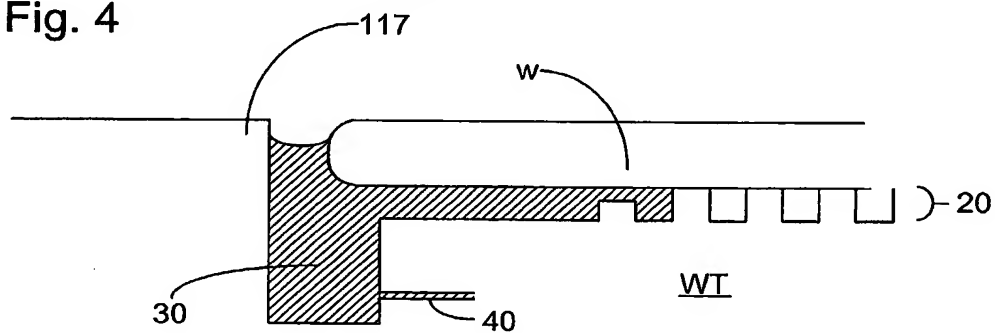


Fig. 5

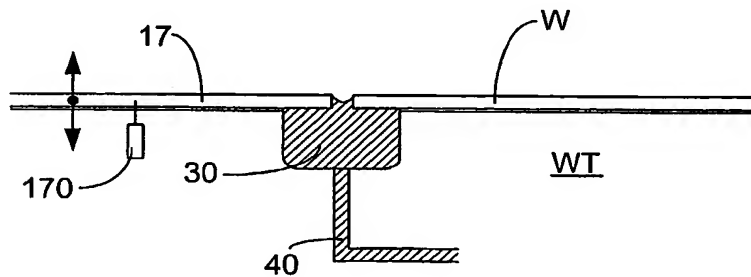


Fig. 6

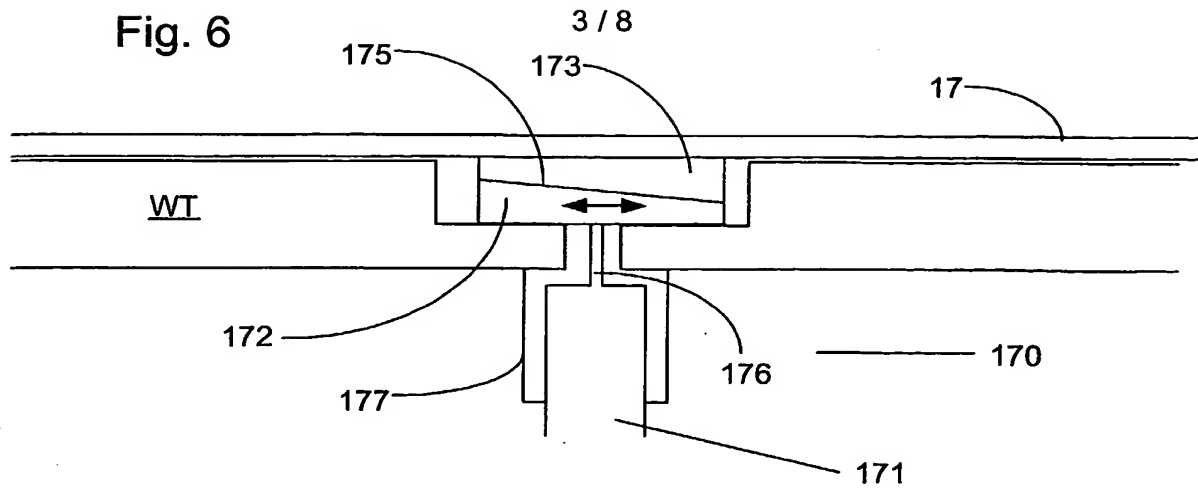


Fig. 7

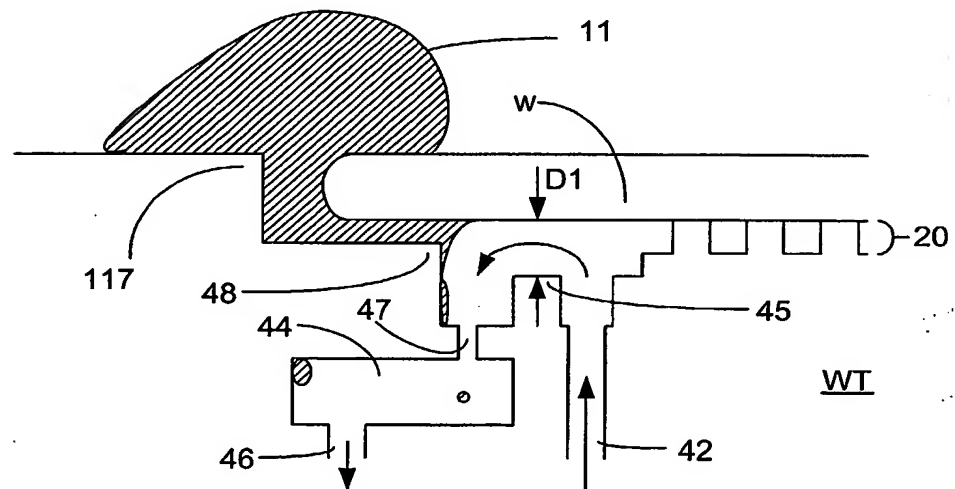


Fig. 8a

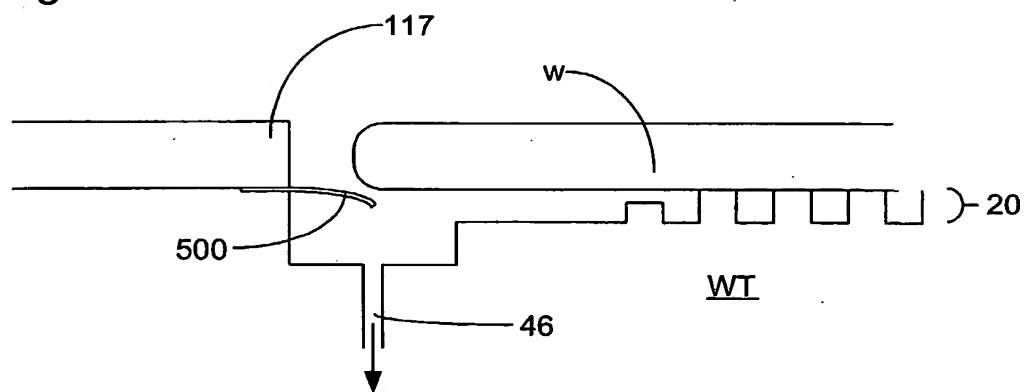


Fig. 8b

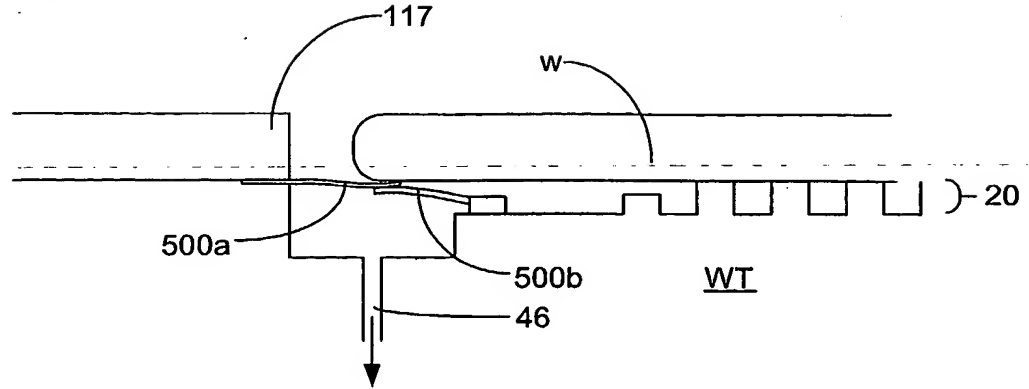


Fig. 8c

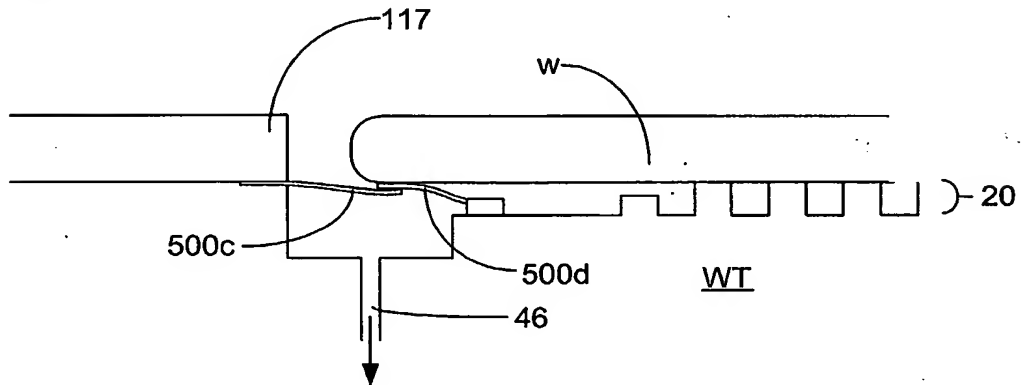


Fig. 9

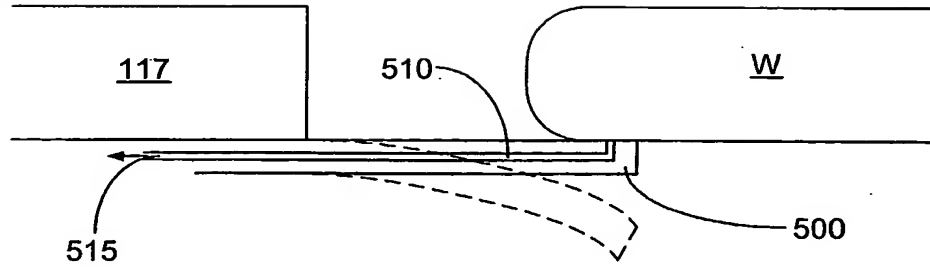


Fig. 10

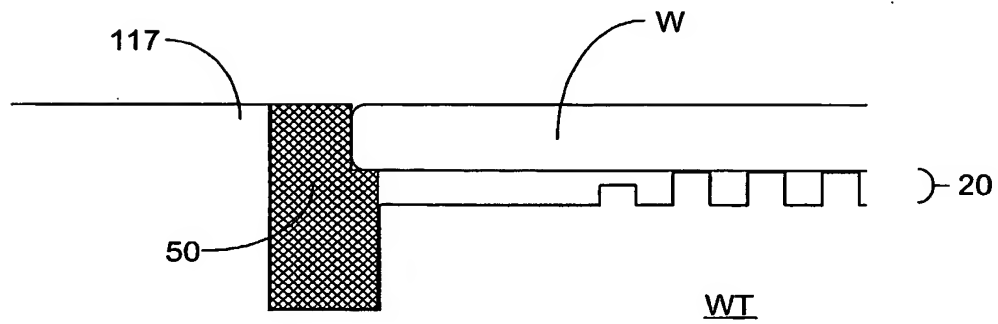


Fig. 11

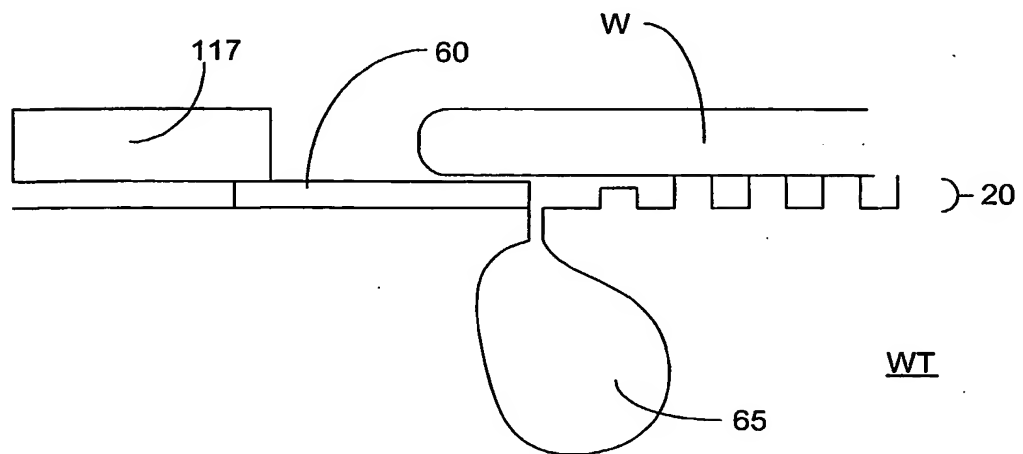


Fig. 12

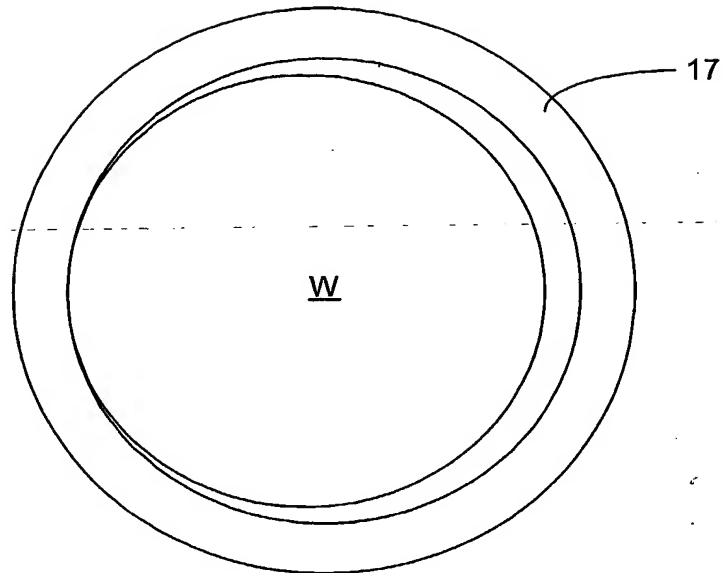


Fig. 13

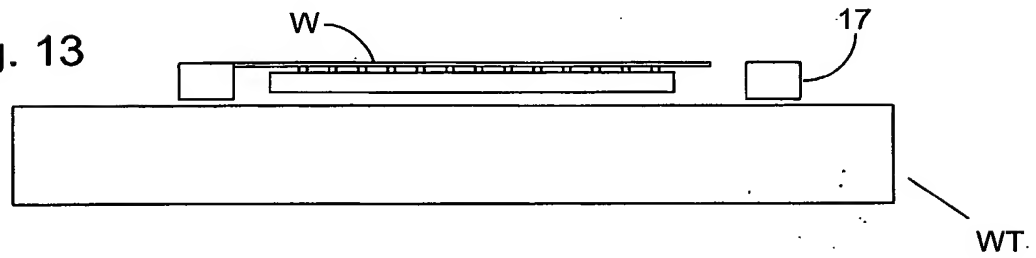


Fig. 14

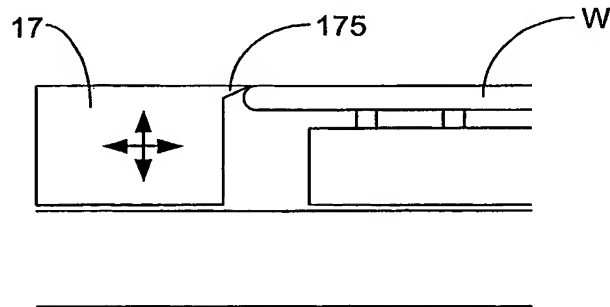


Fig. 15

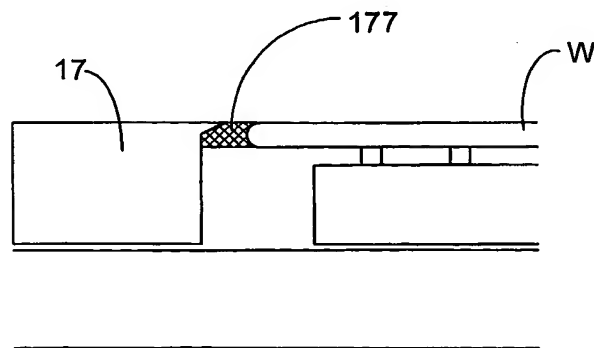


Fig. 16

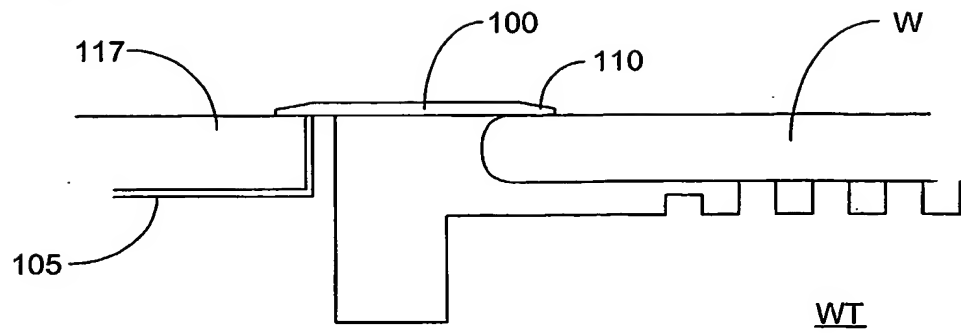


Fig. 17

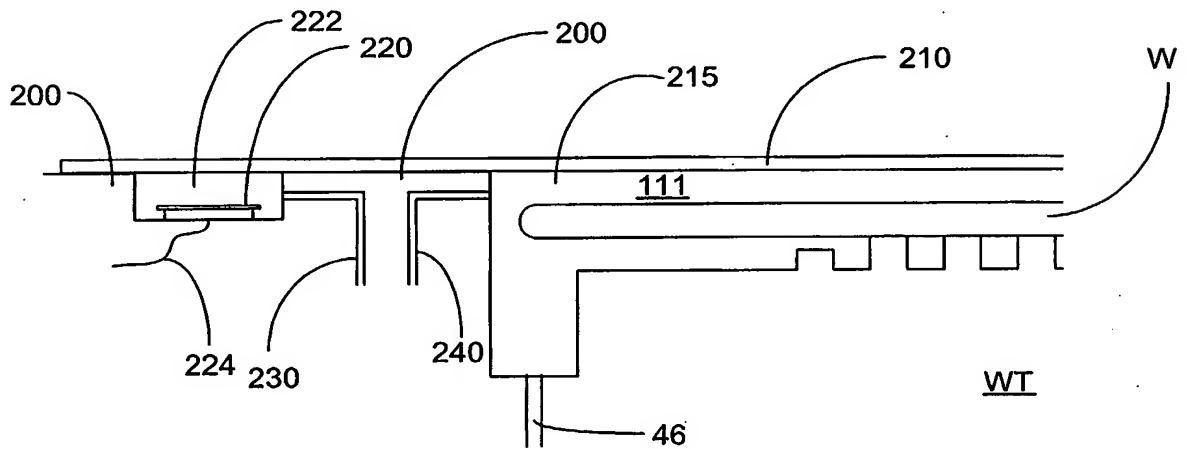


Fig. 18

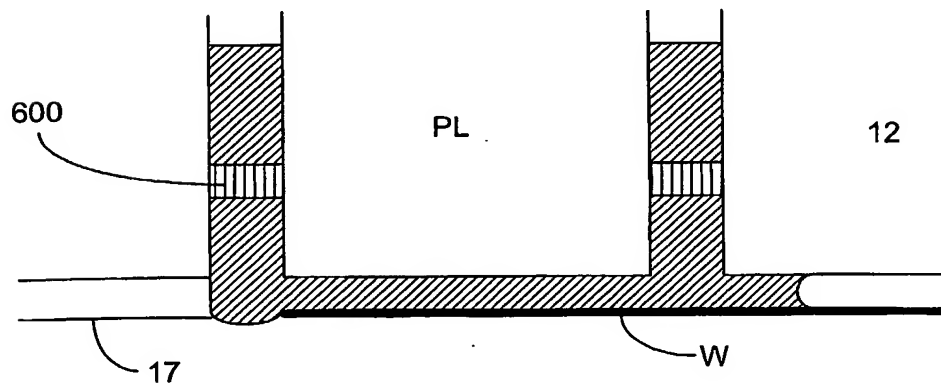


Fig. 19

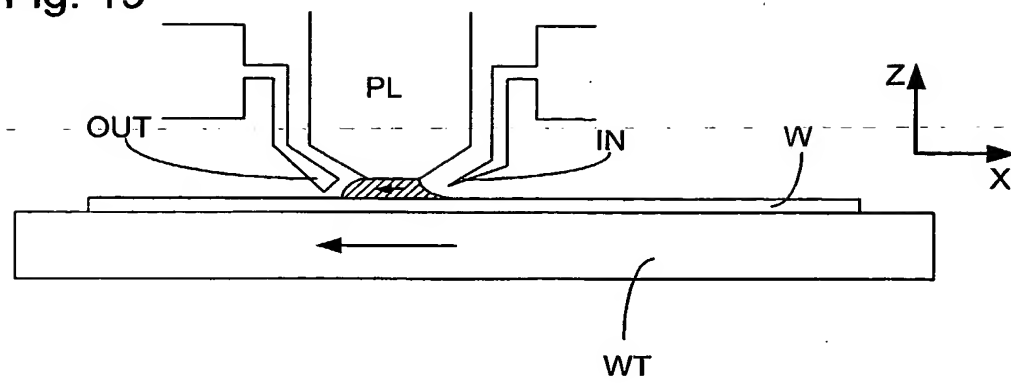


Fig. 20

